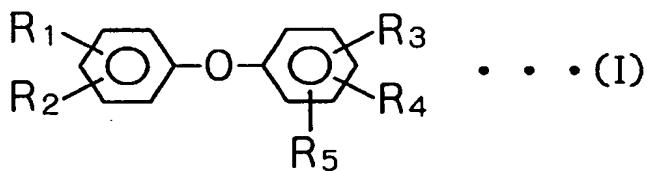


## ABSTRACT

A developer composition for resists which has a high dissolution rate (high developing sensitivity). The developer composition for resists is a developer composition for resists, comprising an organic quaternary ammonium base as a main component and a surfactant, said surfactant containing an anionic surfactant represented by the following general formula (I):



wherein at least one member of R<sub>1</sub> and R<sub>2</sub> represents an alkyl or alkoxy group having 5 to 18 carbon atoms and any remainder member represents a hydrogen atom, or an alkyl or alkoxy group having 5 to 18 carbon atoms, and at least one member of R<sub>3</sub>, R<sub>4</sub> and R<sub>5</sub> represents a group represented by the following general formula (II):

[Chemical Formula 2]



wherein M represents a metal atom, and any remainder member represents a hydrogen atom or a group represented by the above general formula (II).